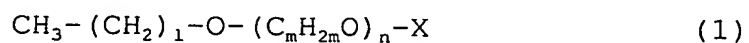
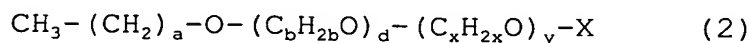


ABSTRACT OF THE DISCLOSURE

A cleaning solution for semiconductor substrates comprising a nonionic surface active agent of the formula (1) and/or the formula (2), a chelating agent and a chelating accelerator:



wherein 1, m and n independently represent a positive number, and X represents a hydrogen atom or a hydrocarbon group;



wherein a, b, d, x and y independently represent a positive number, b and x are different, and X represents a hydrogen atom or a hydrocarbon group.